

L Number	Hits	Search Text	DB	Time stamp
1	10	koshiro near ochiai.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/10 13:07
2	7360	(methacrylate or acrylate) and wash\$3 and oxalic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/10 13:09
3	553	(methacrylate or acrylate) and wash\$3 same oxalic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/10 13:09
4	532	(methacrylate or acrylate) and wash\$3 same oxalic near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/10 13:10
5	95186	metal near3 remov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/10 13:11
6	40	(metal near3 remov\$3) and ((methacrylate or acrylate) and wash\$3 same oxalic near acid)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/10 13:11
-	496664	poly(meth)acrylate and metal near content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 14:14
-	496901	poly(meth)acrylate and metal near content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:05
-	4530	(poly(meth)acrylate and metal near content) and solvent near extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:00
-	412	((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:02
-	0	((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:03
-	28	((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polycarboxylic near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:03
-	496458	poly(meth)acrylate same metal near content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:06
-	496443	poly(meth)acrylate same reduced near metal near content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:13
-	496459	poly(meth)acrylate same reduced same metal same content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:08
-	504390	poly(meth)acrylate same metal	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:09

-	853	(poly(meth)acrylate same reduced same metal same content) same solvent same extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:14
-	63722	solvent same extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:14
-	4	((poly(meth)acrylate same reduced same metal same content) same solvent same extraction) same aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:19
-	496858	poly(meth)acrylate same photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:17
-	3	polyacrylate same photoresist and metal near content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 14:21
-	159	polyacrylate same photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:06
-	887236	poly(meth)acrylate same photoresistsame purif\$8	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:17
-	496445	poly(meth)acrylate same photoresist same purif\$8	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:26
-	497666	poly(meth)acrylate same purif\$8	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:18
-	1367	(poly(meth)acrylate same photoresist same purif\$8) same metal same content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:19
-	40	((poly(meth)acrylate same photoresist same purif\$8) same metal same content) and wash\$3 near3 acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:20
-	245857	purif\$8 same process same poly(meth)acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:28
-	17	(purif\$8 same process same poly(meth)acrylate) and reduced near metal near content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:31
-	8	ochiai near koshiro.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:49
-	3	"6258507"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:50
-	252194	purif\$8 same poly(meth)acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:51

-	1256	(purif\$8 same poly(meth)acrylate) same photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 17:06
-	4	((purif\$8 same poly(meth)acrylate) same photoresist) same metal same content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:53
-	36	((purif\$8 same poly(meth)acrylate) same photoresist) and metal same content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 16:53
-	8	((purif\$8 same poly(meth)acrylate) same photoresist) same metal near ions	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 17:09
-	820	metal near ions near removal	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:13
-	80	(purif\$8 same poly(meth)acrylate) and (metal near ions near removal)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 17:16
-	12	(metal near ions near removal) same aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 17:26
-	1	(metal near ions near removal) and wash\$3 near aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/02 17:27
-	235455	purif\$7 near poly(meth)acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:52
-	24269	wash near aqueous near acid or solvent near extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:54
-	41	wash near aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:54
-	2131	(purif\$7 near poly(meth)acrylate) and (wash near aqueous near acid or solvent near extraction)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:54
-	276	aqueous near acid near extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:54
-	9485	aqueous near acid and extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:55
-	36	(purif\$7 near poly(meth)acrylate) and (aqueous near acid near extraction)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:56
-	0	polyacrylate and purif7	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:56

-	4409	polyacrylate and purif\$7	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 10:08
-	7450	polyacrylate and purif\$7	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:57
-	248	(polyacrylate and purif\$7) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 09:57
-	4	polyacrylate and trace near metal near ion near remov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 10:09
-	40	(polyacrylate and metal near ion near remov\$3) and wash	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 10:11
-	120	polyacrylate and metal near ion near remov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 10:11
-	169038	polymerization and poly(meth)acrylate and extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:08
-	100	(polymerization and poly(meth)acrylate and extraction) and aqueous near oxalic near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 14:16
-	845	(polymerization and poly(meth)acrylate and extraction) and metal near remov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 15:04
-	102	((polymerization and poly(meth)acrylate and extraction) and metal near remov\$3) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 14:23
-	0	((polymerization and poly(meth)acrylate and extraction) and metal near remov\$3) and aqueous near oxalic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 15:04
-	101	(polymerization and poly(meth)acrylate and extraction) and aqueous near oxalic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 15:04
-	4575	(polymerization and poly(meth)acrylate and extraction) and aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 15:59
-	78	((polymerization and poly(meth)acrylate and extraction) and aqueous near acid) and ((polymerization and poly(meth)acrylate and extraction) and metal near remov\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 15:59
-	3585	(polymerization and poly(meth)acrylate and extraction) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:09
-	136	((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:19

-	496582	poly(meth)acrylate with reduc\$4 near metal near content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:21
-	496590	poly(meth)acrylate with reduc\$4 with metal with content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:22
-	1844	(poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:23
-	0	((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvnt near extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:24
-	0	((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:24
-	50	((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:29
-	18	((poly(meth)acrylate same photoresist same purif\$8) same metal same content) and washing near3 acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:38
-	814287	process same reduc\$3 metal same poly(meth)acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:40
-	870738	method same reduc\$3 metal same poly(meth)acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:02
-	792291	process same reduc\$3 metal same content same poly(meth)acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:57
-	32	(process same reduc\$3 metal same content same poly(meth)acrylate) and wash near aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:42
-	797019	process same reduc\$3 metal same content and poly(meth)acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:57
-	660739	process same reduc\$3 metal same content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:59
-	2	contact\$3 near solvent near aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 16:59
-	3600	(process same reduc\$3 metal same content) and polymethacrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:01
-	0	((process same reduc\$3 metal same content) and polymethacrylate) and (extract\$4 near solvent near aqueous near acid)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:00

-	15	extract\$4 near solvent near aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:00
-	166	((process same reduc\$3 metal same content) and polymethacrylate) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:01
-	2590	(method same reduc\$3 metal same poly(meth)acrylate) and ((process same reduc\$3 metal same content) and polymethacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:02
-	138	((method same reduc\$3 metal same poly(meth)acrylate) and ((process same reduc\$3 metal same content) and polymethacrylate)) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:05
-	1	polyacrylate with reduced with metal with content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:06
-	496728	poly(meth)acrylate with reduced with metal with content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:06
-	0	polymethacrylate with reduced with metal with content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:06
-	5	acrylate with reduced with metal with content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:08
-	225	polymer with reduc\$3 with metal with content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:09
-	142	polymer with reduced with metal with content	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:10
-	3011096	remov\$3 metal near polyacrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:28
-	0	removal near metal near polyacrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:12
-	35	metal near ions near removal and polyacrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:13
-	691	(remov\$3 metal near polyacrylate) and solvent near aqueous near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:25
-	229	((remov\$3 metal near polyacrylate) and solvent near aqueous near acid) and extraction	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:25
-	68007	(remov\$3 metal near polyacrylate) and ion near exchange	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:29

-	2	("5466745").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:44
-	1	("60005045").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:37
-	2	("6005045").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:37
-	2	("6046276").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:42
-	2	("5916992").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:43
-	2	((("5466745").PN.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:44
-	9	"5466745"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/03 17:44
-	350	polymeriz\$5 same acrylate same aqueous same acid same solvent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:09
-	5	(polymeriz\$5 same acrylate same aqueous same acid same solvent) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:09
-	31	polymeriz\$5 same acrylate same extract\$3 same aqueous same acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:14
-	18	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:15
-	220	polymeriz\$5 same acrylate same wash\$3 same aqueous same acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:17
-	19	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:17
-	7	Synthesi\$4 same acrylate same wash\$3 same aqueous same acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:19
-	204	polymeriz\$5 same acrylate same wash\$3 same aqueous same acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 12:24
-	4	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and metal near remov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:20

-	129596	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and maleic or fumaric or oxalic or malonic or adipic near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 12:26
-	115	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and (maleic or fumaric or oxalic or malonic or adipic near acid)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 12:49
-	7	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and oxalic near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 12:51
-	0	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and aqueous near oxalic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 13:01
-	19	"4089806"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 13:05
-	9	"4122000"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 13:43
-	88	metal near remov\$3 near chelat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 13:44
-	2	(metal near remov\$3 near chelat\$3) and oxalic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 15:29
-	2	("5073622").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 15:33
-	0	a356523	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 15:34
-	0	a356523	JPO; DERWENT	2002/12/04 15:34
-	0	a0356523	JPO; DERWENT	2002/12/04 15:34
-	13	"0356523"	JPO; DERWENT	2002/12/04 15:37
-	2	"03056523"	JPO; DERWENT	2002/12/04 15:50
-	2	("4522928").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 15:50